6.012 Microelectronic Devices and Circuits

Formula Sheet for the Final Exam, Fall 2009

Parameter Values:

$q = 1.6x10^{-19} Coul$ $\varepsilon_{o} = 8.854x10^{-14} F/cm$ $\varepsilon_{r,Si} = 11.7$, $\varepsilon_{Si} \approx 10^{-12} F/cm$ $n_{i}[Si@R.T] \approx 10^{10} cm^{-3}$ $kT/q \approx 0.025 V$; $(kT/q) \ln 10 \approx 0.06 V$ $1 \mu m = 1x10^{-4} cm$

Periodic Table:

Electrostatics:

<u>III</u>	<u>IV</u>	V
В	C	N
Al	Si	P
Ga	Ge	As
In	Sn	Sb

Drift/Diffusion:

Drift velocity: $\bar{s}_x = \pm \mu_m E_x$ $\varepsilon \frac{dE(x)}{dx}$ Conductivity: $\sigma = q(\mu_e n + \mu_h p)$ $-\frac{d\phi(x)}{dx}$ Diffusion flux: $F_m = -D_m \frac{\partial C_m}{\partial x}$ $\frac{d^2\phi(x)}{dx}$

$\varepsilon \frac{dE(x)}{dx} = \rho(x)$ $E(x) = \frac{1}{2} \int \rho(x) dx$

$$-\frac{d\phi(x)}{dx} = E(x) \qquad \phi(x) = -\int E(x)dx$$

$$-\varepsilon \frac{d^2\phi(x)}{dx^2} = \rho(x) \qquad \phi(x) = -\frac{1}{\varepsilon} \iint \rho(x)dxdx$$

The Five Basic Equations:

Einstein relation: $\frac{D_m}{u_m} = \frac{kT}{q}$

Electron continuity:
$$\frac{\partial n(x,t)}{\partial t} - \frac{1}{q} \frac{\partial J_e(x,t)}{\partial x} = g_L(x,t) - \left[n(x,t) \cdot p(x,t) - n_i^2 \right] r(T)$$

Hole continuity:
$$\frac{\partial p(x,t)}{\partial t} + \frac{1}{a} \frac{\partial J_h(x,t)}{\partial x} = g_L(x,t) - \left[n(x,t) \cdot p(x,t) - n_i^2 \right] r(T)$$

Electron current density:
$$J_e(x,t) = q\mu_e n(x,t)E(x,t) + qD_e \frac{\partial n(x,t)}{\partial x}$$

Hole current density:
$$J_h(x,t) = q\mu_h p(x,t) E(x,t) - qD_h \frac{\partial p(x,t)}{\partial x}$$

Poisson's equation:
$$\frac{\partial E(x,t)}{\partial x} = \frac{q}{\varepsilon} \Big[p(x,t) - n(x,t) + N_d^+(x) - N_a^-(x) \Big]$$

Uniform doping, full ionization, TE

n-type,
$$N_d \gg N_a$$

 $n_o \approx N_d - N_a \equiv N_D$, $p_o = n_i^2/n_o$, $\phi_n = \frac{kT}{q} \ln \frac{N_D}{n_i}$
p-type, $N_a \gg N_d$
 $p_o \approx N_a - N_d \equiv N_A$, $n_o = n_i^2/p_o$, $\phi_p = -\frac{kT}{q} \ln \frac{N_A}{n_i}$

Uniform optical excitation, uniform doping

$$n = n_o + n' \qquad p = p_o + p' \qquad n' = p' \qquad \frac{dn'}{dt} = g_l(t) - (p_o + n_o + n')n'r$$
Low level injection, n',p' << p_o + n_o:
$$\frac{dn'}{dt} + \frac{n'}{\tau_{\min}} = g_l(t) \quad \text{with} \quad \tau_{\min} \approx (p_o r)^{-1}$$

Flow problems (uniformly doped quasi-neutral regions with quasi-static excitation and low level injection; p-type example):

Minority carrier excess:
$$\frac{d^2n'(x)}{dx^2} - \frac{n'(x)}{L_e^2} = -\frac{1}{D_e}g_L(x) \qquad L_e = \sqrt{D_e\tau_e}$$

Minority carrier current density:
$$J_e(x) \approx qD_e \frac{dn'(t)}{dx}$$

Majority carrier current density:
$$J_h(x) = J_{Tot} - J_e(x)$$

Electric field:
$$E_x(x) \approx \frac{1}{q\mu_h p_o} \left[J_h(x) + \frac{D_h}{D_e} J_e(x) \right]$$

Majority carrier excess:
$$p'(x) \approx n'(x) + \frac{\varepsilon}{q} \frac{dE_x(x)}{dx}$$

Short base, infinite lifetime limit:

Minority carrier excess:
$$\frac{d^2n'(x)}{dx^2} \approx -\frac{1}{D_e}g_L(x), \quad n'(x) \approx -\frac{1}{D_e}\iint g_L(x)dxdx$$

Non-uniformly doped semiconductor sample in thermal equilibrium

$$\frac{d^{2}\phi(x)}{dx^{2}} = \frac{q}{\varepsilon} \left\{ n_{i} \left[e^{q\phi(x)/kT} - e^{-q\phi(x)/kT} \right] - \left[N_{d}(x) - N_{a}(x) \right] \right\}$$

$$n_{o}(x) = n_{i} e^{q\phi(x)/kT}, \quad p_{o}(x) = n_{i} e^{-q\phi(x)/kT}, \quad p_{o}(x) n_{o}(x) = n_{i}^{2}$$

Depletion approximation for abrupt p-n junction:

$$\rho(x) = \begin{cases} 0 & \text{for } x < -x_{p} \\ -qN_{Ap} & \text{for } -x_{p} < x < 0 \\ qN_{Dn} & \text{for } 0 < x < x_{n} \\ 0 & \text{for } x_{n} < x \end{cases} \qquad b_{Ap}x_{p} = N_{Dn}x_{n}$$

$$\psi_{b} = \phi_{n} - \phi_{p} = \frac{kT}{q} \ln \frac{N_{Dn}N_{Ap}}{n_{i}^{2}}$$

$$w(v_{AB}) = \sqrt{\frac{2\varepsilon_{Si} (\phi_{b} - v_{AB})}{q} \frac{(N_{Ap} + N_{Dn})}{N_{Ap}N_{Dn}}} \qquad |E_{pk}| = \sqrt{\frac{2q (\phi_{b} - v_{AB})}{\varepsilon_{Si}} \frac{N_{Ap}N_{Dn}}{(N_{Ap} + N_{Dn})}}$$

$$q_{DP}(v_{AB}) = -AqN_{Ap}x_{p}(v_{AB}) = -A\sqrt{2q\varepsilon_{Si} (\phi_{b} - v_{AB}) \frac{N_{Ap}N_{Dn}}{(N_{Ap} + N_{Dn})}}$$

<u>Ideal p-n junction diode i-v relation:</u>

$$n(-x_{p}) = \frac{n_{i}^{2}}{N_{Ap}} e^{qv_{AB}/kT}, \quad n'(-x_{p}) = \frac{n_{i}^{2}}{N_{Ap}} \left(e^{qv_{AB}/kT} - 1 \right); \qquad p(x_{n}) = \frac{n_{i}^{2}}{N_{Dn}} e^{qv_{AB}/kT}, \quad p'(x_{n}) = \frac{n_{i}^{2}}{N_{Dn}} \left(e^{qv_{AB}/kT} - 1 \right)$$

$$i_{D} = Aq n_{i}^{2} \left[\frac{D_{h}}{N_{Dn}w_{n,eff}} + \frac{D_{e}}{N_{Ap}w_{p,eff}} \right] \left[e^{qv_{AB}/kT} - 1 \right] \qquad w_{m,eff} = \begin{cases} w_{m} - x_{m} & \text{if } L_{m} >> w_{m} \\ L_{m} & \text{if } L_{m} << w_{m} \end{cases}$$

$$L_{m} \qquad if \quad L_{m} << w_{m}$$

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$$Note: p'(x) \approx p'(x) \text{ in ONRs}$$

$$q_{QNR,p\text{-}side} = Aq \int_{-w_n}^{-x_p} n'(x) dx, \qquad q_{QNR,n\text{-}side} = Aq \int_{x_n}^{w_n} p'(x) dx, \qquad \text{Note: } p'(x) \approx n'(x) \text{ in QNRs}$$

<u>Large signal BJT Model in Forward Active Region (FAR)</u>:

(npn with base width modulation)

$$i_{B}(v_{BE},v_{CE}) = I_{BS}\left(e^{qv_{BE}/kT} - 1\right)$$

$$i_{C}(v_{BE},v_{BC}) = \beta_{F} i_{B}(v_{BE},v_{CE})\left[1 + \lambda v_{CE}\right] = \beta_{F}I_{BS}\left(e^{qv_{BE}/kT} - 1\right)\left[1 + \lambda v_{CE}\right]$$
with:
$$I_{BS} = \frac{I_{ES}}{(\beta_{F} + 1)} = \frac{Aqn_{i}^{2}}{(\beta_{F} + 1)}\left(\frac{D_{h}}{N_{DE}w_{E,eff}} + \frac{D_{e}}{N_{AB}w_{B,eff}}\right), \quad \beta_{F} = \frac{\alpha_{F}}{(1 - \alpha_{F})}, \text{ and } \quad \lambda = \frac{1}{V_{A}}$$
Also,
$$\alpha_{F} = \frac{(1 - \delta_{B})}{(1 + \delta_{E})} \quad \text{and} \quad \beta_{F} \approx \frac{(1 - \delta_{B})}{(\delta_{E} + \delta_{B})} \quad \text{with} \quad \delta_{E} = \frac{D_{h}}{D_{e}} \cdot \frac{N_{AB}}{N_{DE}} \cdot \frac{w_{B,eff}}{w_{E,eff}} \quad \text{and} \quad \delta_{B} = \frac{w_{B,eff}^{2}}{2L_{eB}^{2}}$$
When
$$\delta_{B} \approx 0 \quad \text{then} \quad \alpha_{F} \approx \frac{1}{(1 + \delta_{F})} \quad \text{and} \quad \beta_{F} \approx \frac{1}{\delta_{F}}$$

MOS Capacitor:

Flat - band voltage:
$$V_{FB} \equiv v_{GB}$$
 at which $\phi(0) = \phi_{p-Si}$ [$\Delta \phi = 0$ in Si]
$$V_{FB} = \phi_{p-Si} - \phi_m$$

Threshold voltage:
$$V_T = v_{GC}$$
 at which $\phi(0) = -\phi_{p-Si} - v_{BC}$
$$\left[\Delta \phi = \left| 2\phi_{p-Si} \right| - v_{BC} \text{ in Si} \right]$$

$$V_T(v_{BC}) = V_{FB} - 2\phi_{p-Si} + \frac{1}{C_{ox}^*} \left\{ 2\varepsilon_{Si} q N_A \left[\left| 2\phi_{p-Si} \right| - v_{BC} \right] \right\}^{1/2}$$

Depletion region width at threshold:
$$x_{DT}(v_{BC}) = \sqrt{\frac{2\varepsilon_{Si} \left[\left| 2\phi_{p-Si} \right| - v_{BC} \right]}{qN_A}}$$

Oxide capacitance per unit area:
$$C_{ox}^* = \frac{\varepsilon_{ox}}{t_{ox}}$$
 $\left[\varepsilon_{r,SiO_2} = 3.9, \quad \varepsilon_{SiO_2} \approx 3.5 \times 10^{-13} \ F/cm\right]$

Inversion layer sheet charge density:
$$q_N^* = -C_{ox}^* [v_{GC} - V_T(v_{BC})]$$

Accumulation layer sheet charge density:
$$q_P^* = -C_{ox}^* [v_{GB} - V_{FB}]$$

Gradual Channel Approximation for MOSFET Characteristics:

(n-channel; strong inversion; with channel length modulation; no velocity saturation) Only valid for $v_{BS} \le 0$, $v_{DS} \ge 0$.

$$\begin{split} i_{G}(v_{GS},v_{DS},v_{BS}) &= 0, & i_{B}(v_{GS},v_{DS},v_{BS}) &= 0 \\ i_{D}(v_{GS},v_{DS},v_{BS}) &= \begin{cases} 0 & \text{for } \left[v_{GS}-V_{T}(v_{BS})\right] < 0 < \alpha v_{DS} \\ \frac{K}{2\alpha} \left[v_{GS}-V_{T}(v_{BS})\right]^{2} \left[1+\lambda \left(v_{DS}-v_{DS,sat}\right)\right] & \text{for } 0 < \left[v_{GS}-V_{T}(v_{BS})\right] < \alpha v_{DS} \\ K \left\{v_{GS}-V_{T}(v_{BS})-\alpha \frac{v_{DS}}{2}\right\} v_{DS} & \text{for } 0 < \alpha v_{DS} < \left[v_{GS}-V_{T}(v_{BS})\right] \end{cases} \end{split}$$
 with $V_{T}(v_{BS}) \equiv V_{FB}-2\phi_{p-Si}+\frac{1}{C^{*}}\left\{2\varepsilon_{Si}qN_{A}\left[\left|2\phi_{p-Si}\right|-v_{BS}\right]\right\}^{1/2}, \quad v_{DS,sat} \equiv \frac{1}{\alpha}\left[v_{GS}-V_{T}(v_{BS})\right] \end{split}$

ith
$$V_T(v_{BS}) = V_{FB} - 2\phi_{p-Si} + \frac{1}{C_{ox}^*} \left\{ 2\varepsilon_{Si}qN_A \left[|2\phi_{p-Si}| - v_{BS} \right] \right\}$$
, $V_{DS,sat} = \frac{1}{\alpha} \left[v_{GS} - V_T(v_{BS}) \right]$

$$K = \frac{W}{L} \mu_e C_{ox}^*, \qquad C_{ox}^* = \frac{\varepsilon_{ox}}{t_{ox}}, \qquad \alpha = 1 + \frac{1}{C_{ox}^*} \left\{ \frac{\varepsilon_{Si}qN_A}{2\left[|2\phi_{p-Si}| - v_{BS} \right]} \right\}^{1/2}, \qquad \lambda = \frac{1}{V_A}$$

<u>Large Signal Model for MOSFETs Operated below Threshold (weak inversion)</u>: (n-channel) Only valid for for $v_{GS} \le V_T$, $v_{DS} \ge 0$, $v_{BS} \le 0$.

$$\begin{split} i_{G}(v_{GS}, v_{DS}, v_{BS}) &= 0, & i_{B}(v_{GS}, v_{DS}, v_{BS}) \approx 0 \\ i_{D,s-t}(v_{GS}, v_{DS}, v_{BS}) \approx I_{S,s-t} e^{q\{v_{GS} - V_{T}(v_{BS})\}/nkT} \left(1 - e^{-qv_{DS}/kT}\right) & \text{where } I_{S,s-t} \equiv \frac{W}{2L} \mu_{e} \left(\frac{kT}{q}\right)^{2} \sqrt{\frac{2\varepsilon_{Si}qN_{A}}{\left|2\phi_{p}\right| - v_{BS}}} &= \frac{K_{o}V_{t}^{2}\gamma}{2\sqrt{\left|2\phi_{p}\right| - v_{BS}}} \\ & \text{with } V_{t} \equiv \frac{kT}{q}, \quad K_{o} \equiv \frac{W}{L} \mu_{e} C_{ox}^{*}, \quad \gamma \equiv \frac{\sqrt{2\varepsilon_{Si}qN_{A}}}{C_{ox}^{*}}, \quad n \approx 1 + \frac{\gamma}{2\sqrt{\left|2\phi_{p}\right| - v_{BS}}} \end{split}$$

<u>Large Signal Model for MOSFETs Reaching Velocity Saturation at Small v_{DS} :</u> (n-channel) Only valid for $v_{BS} \le 0$, $v_{DS} \ge 0$. Neglects $v_{DS}/2$ relative to $(v_{CS}-V_T)$.

Saturation model:
$$s_{y}(E_{y}) = \mu_{e}E_{y}$$
 if $E_{y} \leq E_{crit}$, $s_{y}(E_{y}) = \mu_{e}E_{crit} \equiv s_{sat}$ if $E_{y} \geq E_{crit}$ if $i_{G}(v_{GS}, v_{DS}, v_{BS}) = 0$, $i_{B}(v_{GS}, v_{DS}, v_{BS}) = 0$

$$\begin{cases} 0 & \text{for } (v_{GS} - V_{T}) < 0 < v_{DS} \\ W s_{sat} C_{ox}^{*} [v_{GS} - V_{T}(v_{BS})] [1 + \lambda (v_{DS} - E_{crit}L)] & \text{for } 0 < (v_{GS} - V_{T}), E_{crit}L < v_{DS} \\ \frac{W}{L} \mu_{e} C_{ox}^{*} [v_{GS} - V_{T}(v_{BS})] v_{DS} & \text{for } 0 < (v_{GS} - V_{T}), v_{DS} < E_{crit}L \end{cases}$$
with $\lambda \equiv 1/V_{A}$

CMOS Performance

Transfer characteristic:

In general:
$$V_{LO}=0$$
, $V_{HI}=V_{DD}$, $I_{ON}=0$, $I_{OFF}=0$
Symmetry: $V_{M}=\frac{V_{DD}}{2}$ and $NM_{LO}=NM_{HI}$ \Rightarrow $K_{n}=K_{p}$ and $\left|V_{Tp}\right|=V_{Tn}$
Minimum size gate: $L_{n}=L_{p}=L_{\min}$, $W_{n}=W_{\min}$, $W_{p}=\left(\mu_{n}/\mu_{p}\right)W_{n}$ [or $W_{p}=\left(s_{sat,n}/s_{sat,p}\right)W_{n}$]

Switching times and gate delay (no velocity saturation):

$$\tau_{Ch \operatorname{arg}e} = \tau_{Disch \operatorname{arg}e} = \frac{2C_L V_{DD}}{K_n [V_{DD} - V_{Tn}]^2}$$

$$C_L = n (W_n L_n + W_p L_p) C_{ox}^* = 3n W_{\min} L_{\min} C_{ox}^* \qquad \text{assumes } \mu_e = 2\mu_h$$

$$\tau_{Min.Cycle} = \tau_{Ch \operatorname{arg}e} + \tau_{Disch \operatorname{arg}e} = \frac{12n L_{\min}^2 V_{DD}}{\mu_e [V_{DD} - V_{Tn}]^2}$$

Dynamic power dissipation (no velocity saturation):

$$\begin{split} P_{dyn@f_{\text{max}}} &= C_L V_{DD}^2 f_{\text{max}} \propto \frac{C_L V_{DD}^2}{\tau_{Min.Cycle}} \propto \frac{\mu_e W_{\text{min}} \varepsilon_{ox} V_{DD} [V_{DD} - V_{Tn}]^2}{t_{ox} L_{\text{min}}} \\ PD_{dyn@f_{\text{max}}} &= \frac{P_{dyn@f_{\text{max}}}}{\text{InverterArea}} \propto \frac{P_{dyn@f_{\text{max}}}}{W_{\text{min}} L_{\text{min}}} \propto \frac{\mu_e \varepsilon_{ox} V_{DD} [V_{DD} - V_{Tn}]^2}{t_{ox} L_{\text{min}}^2} \end{split}$$

Switching times and gate delay (full velocity saturation):

$$\tau_{Ch \operatorname{arg}e} = \tau_{Disch \operatorname{arg}e} = \frac{C_L V_{DD}}{W_{\min} s_{sat} C_{ox}^* [V_{DD} - V_{Tn}]}$$

$$C_L = n (W_n L_n + W_p L_p) C_{ox}^* = 2n W_{\min} L_{\min} C_{ox}^*$$

$$\tau_{Min.Cycle} = \tau_{Ch \operatorname{arg}e} + \tau_{Disch \operatorname{arg}e} = \frac{4n L_{\min} V_{DD}}{s_{sat} [V_{DD} - V_{Tn}]}$$
assumes $s_{sat,e} = s_{sat,h}$

Dynamic power dissipation per gate (full velocity saturation):

$$\begin{split} P_{dyn@f_{\text{max}}} &= C_L V_{DD}^2 f_{\text{max}} \propto \frac{C_L V_{DD}^2}{\tau_{Min.Cycle}} \propto \frac{s_{sat} W_{\text{min}} \varepsilon_{ox} V_{DD} [V_{DD} - V_{Tn}]}{t_{ox}} \\ PD_{dyn@f_{\text{max}}} &= \frac{P_{dyn@f_{\text{max}}}}{\text{InverterArea}} \propto \frac{P_{dyn@f_{\text{max}}}}{W_{\text{min}} L_{\text{min}}} \propto \frac{s_{sat} \varepsilon_{ox} V_{DD} [V_{DD} - V_{Tn}]}{t_{ox} L^2} \end{split}$$

Static power dissipation per gate

$$\begin{split} P_{\textit{static}} &= V_{\textit{DD}} \, I_{\textit{D,off}} \approx V_{\textit{DD}} \, \frac{W_{\min}}{L_{\min}} \, \mu_e \, V_t^2 \, \sqrt{\frac{\varepsilon_{\textit{Si}} q N_A}{2 \, |V_{\textit{BS}}|}} \quad e^{\left\{-V_T\right\}/nV_t} \\ PD_{\textit{static}} &= \frac{P_{\textit{static}}}{\text{Inverter Area}} \propto \, \frac{V_{\textit{DD}}}{L_{\min}^2} \, \mu_e \, V_t^2 \, \sqrt{\frac{\varepsilon_{\textit{Si}} q N_A}{2 \, |V_{\textit{BS}}|}} \quad e^{\left\{-V_T\right\}/nV_t} \end{split}$$

CMOS Scaling Rules - Constant electric field scaling

$$\begin{split} \text{Scaled Dimensions:} \quad & L_{\min} / s \quad W \to W / s \quad t_{ox} \to t_{ox} / s \quad N_A \to s N_A \\ \text{Scaled Voltages:} \quad & V_{DD} / s \quad V_{BS} \to V_{BS} / s \\ \text{Consequences:} \quad & C_{ox}^* \to s C_{ox}^* \quad K \to s K \quad V_T \to V_T / s \\ & \tau \to \tau / s \quad P_{dyn} \to P_{dyn} / s^2 \quad PD_{dyn@f_{\max}} \to PD_{dyn@f_{\max}} \\ & PD_{static} \to s^2 \, e^{(s-1)V_T / s \, n \, V_t} \, PD_{static} \end{split}$$

Device transit times

Short Base Diode transit time:
$$\tau_b = \frac{w_B^2}{2D_{\min,B}} = \frac{w_B^2}{2\mu_{\min,B}V_{thermal}}$$

Channel transit time, MOSFET w.o. velocity saturation:
$$\tau_{Ch} = \frac{2}{3} \frac{L^2}{\mu_{Ch} |V_{GS} - V_T|}$$

Channel transit time, MOSFET with velocity saturation:
$$\tau_{Ch} = \frac{L}{s_{sat}}$$

Small Signal Linear Equivalent Circuits:

• p-n Diode (n⁺-p doping assumed for C_d)

$$g_d = \frac{\partial i_D}{\partial v_{AB}} \bigg|_Q = \frac{q}{kT} I_S e^{qV_{AB}/kT} \approx \frac{qI_D}{kT}, \qquad C_d = C_{dp} + C_{df},$$
where $C_{dp}(V_{AB}) = A \sqrt{\frac{q\varepsilon_{Si}N_{Ap}}{2(\phi_b - V_{AB})}}, \quad \text{and} \quad C_{df}(V_{AB}) = \frac{qI_D}{kT} \frac{\left[w_p - x_p\right]^2}{2D_e} = g_d \tau_d \quad \text{with} \quad \tau_d = \frac{\left[w_p - x_p\right]^2}{2D_e}$

• BIT (in FAR)

$$\begin{split} g_{\scriptscriptstyle m} &= \frac{q}{kT} \beta_{\scriptscriptstyle o} I_{\scriptscriptstyle BS} \, e^{qV_{\scriptscriptstyle BE}/kT} \left[1 + \lambda V_{\scriptscriptstyle CE} \right] \, \approx \, \frac{q \, I_{\scriptscriptstyle C}}{kT}, \qquad \qquad g_{\scriptscriptstyle \pi} = \, \frac{g_{\scriptscriptstyle m}}{\beta_{\scriptscriptstyle o}} \, = \, \frac{q \, I_{\scriptscriptstyle C}}{\beta_{\scriptscriptstyle o} \, kT} \\ g_{\scriptscriptstyle o} &= \, \beta_{\scriptscriptstyle o} I_{\scriptscriptstyle BS} \left[e^{qV_{\scriptscriptstyle BE}/kT} + 1 \right] \lambda \, \approx \, \lambda \, I_{\scriptscriptstyle C} \quad \left(\text{or} \, \approx \, \frac{I_{\scriptscriptstyle C}}{V_{\scriptscriptstyle A}} \right) \\ C_{\scriptscriptstyle \pi} &= \, g_{\scriptscriptstyle m} \tau_{\scriptscriptstyle b} + \, \text{B-E depletion cap. with} \quad \tau_{\scriptscriptstyle b} \equiv \frac{w_{\scriptscriptstyle B}^2}{2D}, \qquad C_{\scriptscriptstyle \mu} \, \colon \, \text{B-C depletion cap.} \end{split}$$

• MOSFET (strong inversion; in saturation, no velocity saturation)

$$g_{m} = K[V_{GS} - V_{T}(V_{BS})][1 + \lambda V_{DS}] \approx \sqrt{2KI_{D}}$$

$$g_{o} = \frac{K}{2}[V_{GS} - V_{T}(V_{BS})]^{2}\lambda \approx \lambda I_{D} \quad \left(\text{or } \approx \frac{I_{D}}{V_{A}}\right)$$

$$g_{mb} = \eta g_{m} = \eta \sqrt{2KI_{D}} \quad \text{with} \quad \eta = -\frac{\partial V_{T}}{\partial v_{BS}}\Big|_{Q} = \frac{1}{C_{ox}^{*}} \sqrt{\frac{\varepsilon_{SI}qN_{A}}{|q\phi_{p}| - V_{BS}}}$$

 $C_{gs} = \frac{2}{3}W L C_{ox}^*,$ C_{sb}, C_{gb}, C_{db} : depletion capacitances

 $C_{gd} = W C_{gd}^*$, where C_{gd}^* is the G-D fringing and overlap capacitance per unit gate length (parasitic)

• MOSFET (strong inversion; in saturation with full velocity saturation)

$$g_{m} = W \, s_{sat} \, C_{ox}^{*}, \qquad g_{o} = \lambda I_{D} = \frac{I_{D}}{V_{A}}, \qquad g_{mb} = \eta \, g_{m} \quad \text{with} \quad \eta = -\frac{\partial V_{T}}{\partial v_{BS}} \bigg|_{Q} = \frac{1}{C_{ox}^{*}} \sqrt{\frac{\varepsilon_{Si} q N_{A}}{\left| q \phi_{p} \right| - V_{BS}}}$$

$$C_{gs} = W \, L \, C_{ox}^{*}, \qquad C_{sb}, C_{gb}, C_{db} : \quad \text{depletion capacitances}$$

$$C_{gd} = W \, C_{gd}^{*}, \quad \text{where } C_{gd}^{*} \text{ is the G-D fringing and overlap capacitance per unit gate length (parasitic)}$$

 $\bullet \quad$ MOSFET (operated sub-threshold; in forward active region; only valid for $v_{bs}=0)$

$$g_{m} = \frac{qI_{D}}{nkT}, \qquad g_{o} = \lambda I_{D} = \frac{I_{D}}{V_{A}}$$

$$C_{gs} = WLC_{ox}^{*} / \sqrt{1 + \frac{2C_{ox}^{*2}(V_{GS} - V_{FB})}{\varepsilon_{Si}qN_{A}}}, \qquad C_{db}: \text{ drain region depletion capacitance}$$

$$C_{gd} = WC_{gd}^{*}, \text{ where } C_{gd}^{*} \text{ is the G-D fringing and overlap capacitance per unit gate length (parasitic)}$$

Single transistor analog circuit building block stages Note: $g_1 = g_{sl} + g_{el}$; $g'_1 = g_o + g_l$

BIPOLAR	Voltage	Current	Input	Output
DIFOLAR	gain, A_v	gain, A _i	resistance, R _i	resistance, R _o
Common emitter	$-\frac{g_m}{\left[g_o+g_l\right]} \left(\approx -g_m r_l\right)$	$-\frac{\beta g_l}{\left[g_o + g_l\right]}$	r_{π}	$r_o \left(= \frac{1}{g_o} \right)$
Common base	$\frac{g_m}{\left[g_o + g_l\right]} \left(\approx g_m r_l \right)$	≈ 1	$\approx \frac{r_{\pi}}{\left[\beta + 1\right]}$	$\approx [\beta + 1]r_o$
Emitter follower	$\frac{\left[g_m + g_\pi\right]}{\left[g_m + g_\pi + g_o + g_l\right]} \approx 1$	$\frac{\beta g_l}{\left[g_o + g_l\right]} \approx \beta$	$r_{\pi} + [\beta + 1]r_{l}$	$\frac{r_t + r_\pi}{\left[\beta + 1\right]}$
Emitter degeneracy	$\approx -\frac{r_l}{R_F}$	$\approx \beta$	$\approx r_{\pi} + [\beta + 1]R_F$	$\approx r_o$
Shunt feedback	$-\frac{\left[g_m - G_F\right]}{\left[g_o + G_F\right]} \approx -g_m R_F$	$-rac{g_{l}}{G_{F}}$	$\frac{1}{g_\pi + G_F \big[1 - A_{_{\boldsymbol{\nu}}} \big]}$	$r_o \parallel R_F \left(= \frac{1}{g_o + G_F} \right)$

MOSFET	Voltage	Current	Input	Output
MOSPET	gain, A _v	gain, A _i	resistance, R _i	resistance, R _o
Common source	$-\frac{g_m}{\left[g_o + g_l\right]} \left(= -g_m r_l \right)$	∞	∞	$r_o \left(=\frac{1}{g_o}\right)$
Common gate	$\approx [g_m + g_{mb}]r_l$	≈ 1	$\approx \frac{1}{\left[g_m + g_{mb}\right]}$	$\approx r_o \left\{ 1 + \frac{\left[g_m + g_{mb} + g_o \right]}{g_t} \right\}$
Source follower	$\frac{\left[g_{m}\right]}{\left[g_{m}+g_{o}+g_{l}\right]}\approx1$	∞	∞	$\frac{1}{\left[g_m + g_o + g_l\right]} \approx \frac{1}{g_m}$
Source degeneracy	$\approx -\frac{r_l}{r_l}$	∞	∞	
(series feedback)	$\approx -\frac{1}{R_F}$	~	~	$\approx r_o$
Shunt feedback	$-\frac{\left[g_m - G_F\right]}{\left[g_o + G_F\right]} \approx -g_m R_F$	$-rac{g_l}{G_F}$	$\frac{1}{G_F[1-A_v]}$	$r_o \parallel R_F \left(= \frac{1}{\left[g_o + G_F\right]} \right)$

OCTC/SCTC Methods for Estimating Amplifier Bandwidth

OCTC estimate of
$$\omega_{HI}$$
: $\omega_{HI} \leq \left[\sum_{i} \left[\omega_{i}\right]^{-1}\right]^{-1} = \left[\sum_{i} R_{i} C_{i}\right]^{-1}$

with R_i defined as the equivalent resistance in parallel with C_i with all other parasitic device capacitors (C_π 's, C_μ 's, C_g 's, etc.) open circuited.

SCTC estimate of
$$\omega_{LO}$$
: $\omega_{LO} \ge \sum_{j} \omega_{j} = \sum_{j} [R_{j}C_{j}]^{-1}$

with R_j defined as the equivalent resistance in parallel with C_j with all other baising and coupling capacitors (C_1 's, C_0 's, C_E 's, C_S 's, etc.) short circuited.

Difference- and Common-mode signals

Given two signals, v_1 and v_2 , we can decompose them into two new signals, one (v_C) that is common to both v_1 and v_2 , and the other (v_D) that makes an equal, but opposite polarity contribution to v_1 and v_2 :

$$v_D \equiv v_1 - v_2$$
 and $v_C \equiv \frac{\left[v_1 + v_2\right]}{2}$ \longrightarrow $v_1 = v_C + \frac{v_D}{2}$ and $v_1 = v_C - \frac{v_D}{2}$

Short circuit current gain unity gain frequency, f_T

$$\omega_{t} \approx \begin{cases} g_{m}/C_{gs} = 3\mu_{Ch}(V_{GS} - V_{T})/2L^{2} = 3s_{Ch}/2L & \text{MOSFET, no vel. sat.} \\ g_{m}/C_{gs} = W s_{sat}C_{ox}^{*}/W LC_{ox}^{*} = s_{sat}/L & \text{MOSFET, w. vel. sat.} \\ g_{m}/(C_{\pi} + C_{\mu}); \lim_{I_{c} \to \infty} \left[g_{m}/(C_{\pi} + C_{\mu}) \right] \approx 2D_{\min,B}/w_{B}^{2} & \text{BJT, large I}_{C} \end{cases} = \frac{1}{\tau_{tr}}$$

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